

IN THE CLAIMS:

Please cancel Claims 1 to 27 without prejudice or disclaimer of subject matter. Please add Claims 28 to 31.

The claims, as pending in the subject application read, as follows:

1 to 27. (Cancelled)

28. (New) A measurement apparatus comprising:

a first detector that measures an intensity of a line-shaped beam from a light source, said first detector configured such that the intensity of the line-shaped beam from the light source is integrated over the entire range of the beam in the vertical direction of the beam;

a second detector for measuring the intensity of the beam at a plurality of points where positions along the vertical direction of the beam are different; and

a calculator for calculating a beam profile in the vertical direction of the beam on the basis of the detections by said first and second detectors.

29. (New) A measurement method comprising the steps of:

measuring an intensity of a line-shaped beam, the intensity being integrated over the entire range of the beam in the vertical direction of the beam;

measuring the intensity of the beam at plurality of points where positions along the vertical direction of the beam are different; and

calculating a beam profile in the vertical direction of the beam on the basis of the respective measurements.

30. (New) An exposure apparatus comprising:
a mirror for reflecting a beam from a light source;
a stage which holds a substrate to be exposed to the beam; and
a measuring device disposed for measuring intensity distribution of the beam irradiating the substrate, the measuring device comprising:
a first detector that measures an intensity of a line-shaped beam, said first detector configured such that the intensity of the line-shaped beam is integrated over the entire range of the beam in the vertical direction of the beam;
a second detector for measuring the intensity of the beam at a plurality of points where positions along the vertical direction of the beam are different; and
calculating means for calculating a beam profile in the vertical direction of the beam on the basis of the detections by said first and second detectors.

31. (New) An exposure apparatus comprising:
a mirror for reflecting a beam from a light source;
a stage which holds a substrate to be exposed to the beam; and
a measuring device having a measuring method for measuring intensity distribution of the line-shaped beam irradiating the substrate, the measuring method comprising:

measuring an intensity of a line-shaped beam, the intensity being integrated over the entire range of the beam in the vertical direction of the beam;

measuring the intensity of the beam at a plurality of points where positions along the vertical direction of the beam are different; and

calculating a beam profile in the vertical direction of the beam on the basis of the respective measurements.